

IN THE ABSTRACT:

Please cancel the current abstract and insert the following.

~~The interior of a port mechanism for exchanging a wafer between a coating/developing system and an exposure apparatus is evacuated, and a predetermined atmospheric gas is introduced. In loading/unloading a wafer into/from the exposure apparatus, the wafer is heated/cooled as needed.~~

A -- An exposure apparatus for exposing a wafer to a pattern includes a chamber in which an atmosphere is conditioned to be different from an atmosphere in another apparatus outside of the exposure apparatus and the wafer is exposed to the pattern, and a port section through which the wafer is transferred between the chamber and the other apparatus, the port section having a load-lock mechanism including a vacuum mechanism for creating a vacuum inside of the port section and a supply mechanism for supplying an inert gas into the inside of the port section.--